

Homework: Photolithography II

Problems 1: Problems 8 in Chapter 7

Problem 2-4: Problems 2, 4, and 5 in Chapter 8

Problem 5: A university lab uses a g-line stepper with $NA = 0.4$ and spatial coherence of 0.5. On a good day, with flat substrates, this machine can resolve 0.8- μm lines and 0.8- μm spaces, but nothing smaller. Find the contrast of the resist being used.